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Patent  
Attorney's Docket No. 027260-295

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of	)	
Kazuya KAMON	)	Group Art Unit: 1756
Application No.: 09/320,946	)	Examiner: S. Mohamedulla
Filed: May 26, 1999	)	Confirmation No.: 5658
For: PHOTOMASK, FABRICATION	)	
METHOD OF PHOTOMASK, AND	)	
FABRICATION METHOD OF	)	
SEMICONDUCTOR INTEGRATED	)	
CIRCUIT	)	

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**PRELIMINARY AMENDMENT**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Date: September 3, 2002

Sir:

This Preliminary Amendment is filed in order to facilitate processing of the above-identified application. Please amend the above-noted application as follows:

**IN THE CLAIMS:**

Please cancel claims 6, 21, 27 and 28 without prejudice and replace claims 1, 2, 5, 7, 8, 13-20 and 22-23 and add new claims 29-49 as follows:

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1. (Amended) A photomask at least comprising:  
  
a transparent substrate;  
  
a hollow section formed on a main surface of said transparent substrate;  
  
a shade pattern formed in said hollow section; and

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